

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Naomasa SHIRAISHI

Attn: PCT Branch

Application No. US National Stage of PCT/JP99/07093

Filed: June 25, 2001

Docket No.: 109919

For: METHOD AND APPARATUS FOR PRODUCING MASK

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PRELIMINARY AMENDMENT

Director of the U.S. Patent and Trademark Office
Washington, D. C. 20231

Sir:

Prior to initial examination, and after entry of the annexes to the IPER, please amend the above-identified application as follows:

CHANGES TO THE ANNEXES TO THE IPER:

Page 1, line 19 to page 2, line 8, delete current paragraph and insert therefor:

Next, a third producing method of a mask of the present invention is a producing method of a mask used for double exposure of a photosensitive substrate, wherein a parent pattern of a master mask is transferred onto a first substrate to produce a first mask used for one exposure of the double exposure, and the parent pattern of the master mask is transferred onto a second substrate to produce a second mask used for the other exposure of the double exposure, and a condition under which the parent pattern of the master mask is transferred to produce the first mask and a condition under which the parent pattern of the master mask is transferred to produce the second mask are different from each other.

Page 2, line 13 to line 21, delete current paragraph and insert therefor:

Further, a fourth producing method of a mask of the present invention is a producing

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